

## Press Release

Nr. 13 from September 25, 2009

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New: OTS™ Oxygen Trap System

### **NETZSCH Grabs Residual Oxygen by the Collar**

Residual oxygen in the analytical chamber is an aggravating and widely occurring problem in thermal analysis. Even the minimal residual oxygen content in a 99.996% helium atmosphere can cause undesired reactions and produce imprecise measurement results.

Get to the root of the problem!

The new OTS™ system allows for effective reduction of the oxygen concentration right at the source: It binds residual oxygen directly in the sample chamber by means of a highly absorbent getter material. The OTS™ system has no direct contact with the sample, since the getter – the core of the OTS™ system – is located beneath the measurement sensor. It is fastened onto a slotted cylindrical mount, so that the OTS™ system can be easily attached and removed. Ascending purge gas first comes into contact with the getter material. Residual oxygen is intercepted there before it ever reaches the sample. The residual oxygen concentration in the purge gas upon reaching the sample then amounts to less than 1 ppm.

The facts speak for OTS

Zirconium, when held isothermally for two hours at 1000°C in a 99.996% dynamic helium atmosphere without OTS, exhibits a continuous gain in mass due to oxidation.

With OTS: There is no gain in mass resulting from oxidation